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MOLECULAR IMPRINTS UPGRADES IMPRIO® 250 SYSTEM TO IMPRIO® 300 AT TOSHIBA

AUSTIN, TX. February 16, 2010 – Molecular Imprints, Inc., the market and technology leader for nanopatterning systems and solutions, today announced that it is upgrading its Imprio® 250 nanopatterning system, installed at the Device Process Development Center of Toshiba’s Corporate Research and Development Center, to an Imprio 300. Molecular Imprints’ Imprio 300 system represents the highest resolution and lowest cost-of-ownership (CoO) patterning solution for IC prototyping and process development. Built upon the Imprio 250 architecture, the Imprio 300 delivers significantly improved throughput rates, overlay performance and automation capabilities. In addition, the ability of the Imprio 300 to create dense, high-resolution structures makes it especially well suited for advanced semiconductor applications.

“Molecular Imprints is dedicated to realize the full potential of our Jet and Flash™ Imprint Lithography (J-FIL™) technology for advanced semiconductor applications,” stated Mark Melliar-Smith, CEO of Molecular Imprints. “The progress we are delivering in terms of tool resolution and cost of ownership performance is evidence that imprint lithography has emerged as one of the candidates for future production of semiconductor devices. In all of the key technical categories from overlay control to defectivity levels, our imprint lithography systems are meeting their benchmarks as we move to support volume production with cutting-edge technology.”

With improved overlay performance, a mix-and-match strategy with existing 193-nm scanners has been demonstrated down to 20nm full field. Utilized in a mix-and-match strategy, J-FIL’s resolution and cost advantages can be deployed on specific critical layers, while its use of commercially available photomasks, exposure sources and resists makes for straightforward integration with the industry’s existing optical lithography infrastructure. Beyond being compatible with the existing lithography infrastructure, J-FIL technology offers the promise of extending lithography to 10nm and beyond.

About Molecular Imprints, Inc.

Molecular Imprints, Inc. (MII) is the technology leader for high-resolution, low cost-of-ownership nanopatterning systems and solutions in the hard disk drive (HDD) and semiconductor industries. MII is leveraging its innovative Jet and Flash™ Imprint Lithography (J-FIL™) technology with IntelliJet™ material application to become the worldwide market and technology leader in high-volume patterning solutions for storage and memory devices, while enabling emerging markets in clean energy, biotechnology, and other industries. MII enables nanoscale patterning by delivering a comprehensive nanopatterning solution that is affordable, compatible and extendible to sub-10-nanometer resolution levels. For more information, visit www.molecularimprints.com.

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